

AMENDMENTS TO THE CLAIMS

1. (Currently amended) ~~Metal~~A metal-containing, hydrogen-storing material that contains ~~[[a]]an~~ organometallic compound as a catalyst for hydrating or dehydrating the same.
2. (Currently amended) ~~Metal~~A metal-containing material according to claim 1, ~~characterised in that~~wherein the organometallic compound is liquid.
3. (Currently amended) ~~Metal~~A metal-containing material according to one of ~~claims 1 or 2, characterised in that this~~claim 1 wherein the material displays a nanocrystalline structure.
4. (Currently amended) ~~Metal~~A metal-containing material according to ~~one of the preceding claims, characterised in that~~claim 1, wherein the organometallic compound displays a nanocrystalline structure.
5. (Currently amended) ~~Metal~~A metal-containing material according to ~~one of the preceding claims, characterised in that~~claim 1, wherein the organometallic compound content lies in the region between 0.005 mol% and 50 mol%.
6. (Currently amended) ~~Metal~~A metal-containing ~~substance~~material according to claim 5, ~~characterised in that~~wherein the organometallic compound content lies in the region between 0.005 mol% and 20 mol%.
7. (Currently amended) ~~Method~~A method for the manufacture of a metal-containing material according to ~~one of the preceding claims, characterised in that~~claim 1, wherein the metal-containing material ~~[[with]]~~containing the organometallic compound is subjected to a mechanical grinding process.
8. (Currently amended) ~~Method~~A method according to claim 7, ~~characterised in that~~wherein the duration of the grinding process is 1 minute to 200 hours.

9. (Currently amended) ~~Method A~~ method according to claim 8, ~~characterised in that wherein~~ the duration of the grinding process lies in the region from 20 hours to 100 hours.

10. (Currently amended) ~~Method A~~ method according to ~~one of claims 7 to 9,~~ ~~characterised in that~~ claim 7 wherein the grinding process is performed in an inert gas atmosphere.

11. (Currently amended) ~~Method A~~ method according to claim 10, ~~characterised in that wherein~~ the inert gas is argon.

12. (Currently amended) ~~Method A~~ method according to ~~one of claims 7 to 11,~~ ~~characterised in that~~ claim 7 wherein the grinding process is performed with the addition of an organic solvent.

13. (New) A metal-containing material according to claim 2, wherein the material displays a nanocrystalline structure.

14. (New) A metal-containing material according to claim 2, wherein the organometallic compound content lies in the region between 0.005 mol% and 50 mol%.

15. (New) A metal-containing material according to claim 4, wherein the organometallic compound content lies in the region between 0.005 mol% and 50 mol%.

16. (New) A method according to claim 9, wherein the grinding process is performed in an inert gas atmosphere.

17. (New) A method according to claim 8, wherein the grinding process is performed with the addition of an organic solvent.

18. (New) A method according to claim 9, wherein the grinding process is performed with the addition of an organic solvent.

19. (New) A method according to claim 10, wherein the grinding process is performed with the addition of an organic solvent.

20. (New) A method according to claim 11, wherein the grinding process is performed with the addition of an organic solvent.